

Deep nanopatterning focused ion beam technology (Technion)**code:** COM-0910

Focused ion beam (FIB) technology is widely used in the semiconductor industry. FIB etching is used to develop and modify optoelectronic and microelectronic devices. However, FIB technology is limited to large scale devices and is incompatible with the industry trend to reduce device dimensions. Our technology is unique and enables nanometric scale FIB lithography.

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